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Application No. 09/921,560

application of etching beams to a sidewall of the first region during etching, wherein the etching mask has a T-shaped cross section.

30. (Amended) An etching mask for selectively etching a workpiece, wherein the etching mask is made of a metal and has a cross-sectional shape comprising a rectangular first region that determines a pattern width of the workpiece, and a second region that intercepts application of etching beams to a sidewall of the first region during etching, wherein the first region is a vertical bar having an end that contacts with a surface of the workpiece, and the second region is a lateral bar placed on another end of the vertical bar and having a width greater than a width of the vertical bar, wherein a pattern width of the workpiece is determined by the width of the vertical bar.

#### REMARKS

Claims 27-37 are pending in this application. By this Amendment, claims 27, 28 and 30 are amended. Claims 33-37 are withdrawn from consideration. No new matter is added. The attached Appendix includes marked-up copies of each rewritten claim (37 C.F.R. §1.121(c)(1)(ii)).

In view of the amendments presented above and the remarks presented below, Applicant respectfully requests that the rejections in the Office Action be reconsidered and withdrawn.

Appreciation is respectfully expressed for the courtesies extended to Applicant's representative by Examiner Collins and Supervisory Primary Examiner Fahmy during the May 28, 2002 personal interview, which resulted in an agreement that claims 28-31 distinguish over the applied art.

Claims 28 and 30, which distinguish over Gulde as memorialized in the summary of the May 28 personal interview, have been amended to be in independent form by explicitly